

Intrinsic Breakdown Strength: Theoretical Derivation and First-Principles Calculations

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Abstract: Intrinsic breakdown strength (F_{bd}), as the theoretical upper limit of electric field strength that a material can sustain, plays important roles in determining dielectric and safety performance. The well accepted concept is that a larger band gap (E_g) often leads to a larger intrinsic breakdown strength. In this work, we analytically derive a simplified model of F_{bd} , showing a linear relationship between F_{bd} and the maximum electron density of states (DOS_{max}) within the energy range spanning from the conduction band minimum (CBM) to $CBM + E_g$. Using the Wannier interpolation technique to reduce the cost of calculating the F_{bd} for various three- and two-dimensional materials, we find that the calculated F_{bd} did not show any simple relationship with band gap, but it behaves linearly with the DOS_{max} , consistent with our theoretical derivation. Our work shows that the DOS_{max} is more fundamental than the band gap value in determining the F_{bd} , thus providing useful physical insights into the intrinsic dielectric breakdown strength and opening directions for improving high-power devices. The dimensional effects on F_{bd} has also been revealed that monolayers tend to have larger F_{bd} due to reduced screening effects.

Introduction

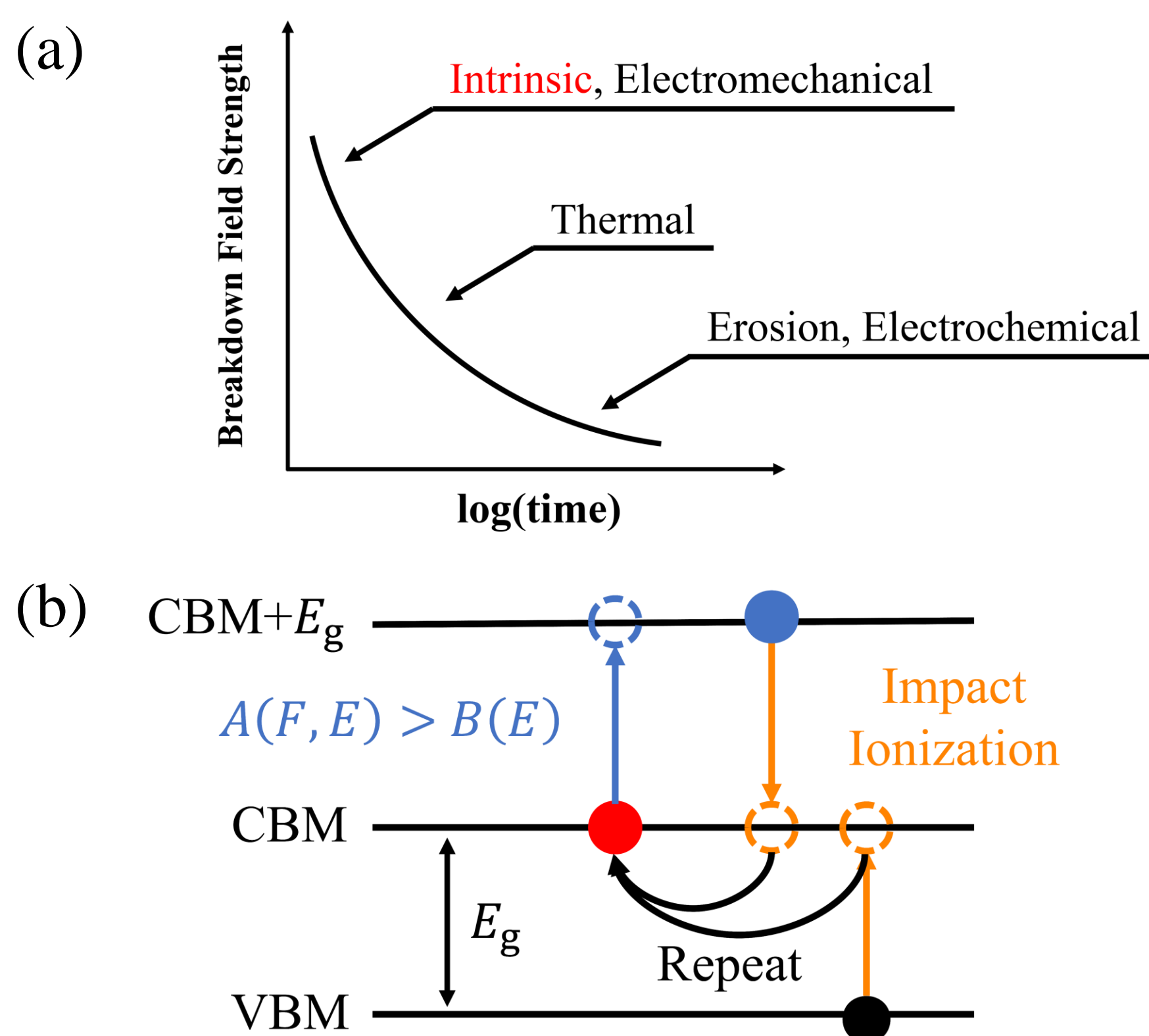


Fig. 1. (a) Comparison between different breakdown mechanism. (b) Schematic diagram for the process of electron avalanche breakdown.

Relation between F_{bd} and $MDOS_{max}$

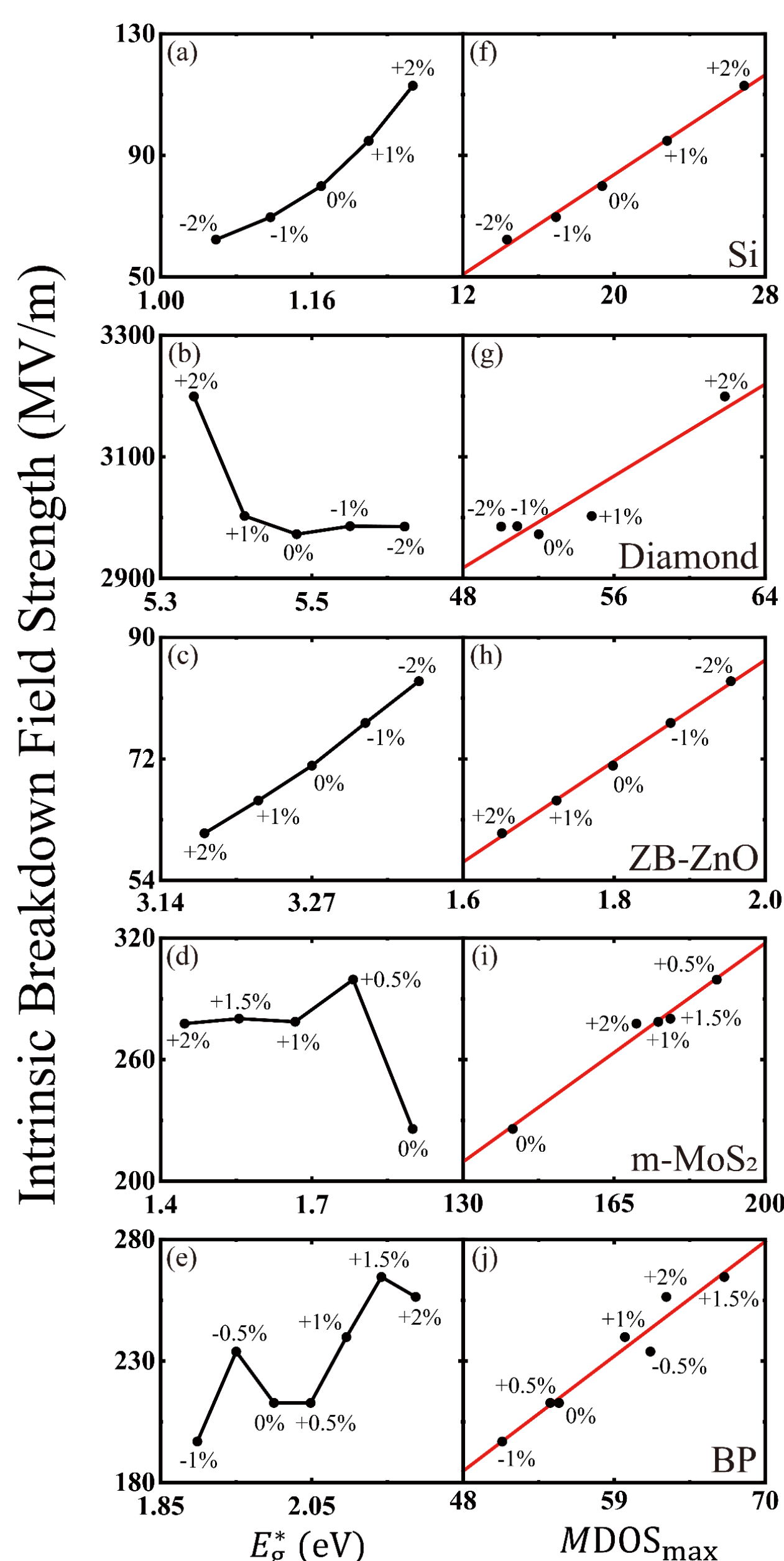


Fig. 2. Comparison of the relation between F_{bd} and band gap with that between F_{bd} and $MDOS_{max}$, where $M = \sqrt{m^* \omega_{mean}}$. Here, the band gap and DOS_{max} are tuned using strains, which are labeled for each data.

- The well accepted concept is that a larger band gap often leads to a larger intrinsic breakdown field strength. However, we found that the calculated F_{bd} did not follow a simple relationship with the band gap.
- It is clearly seen from Fig. 2(f)-(j) that F_{bd} is linearly dependent on the normalized DOS_{max} for each system, even in cases where the prevailing view does not hold, thus demonstrating our model.

Methods

$$\frac{1}{\tau(E)} = \frac{1}{D(E)} \frac{2\pi}{\hbar} \sum_{\pm} \sum_{nk} \sum_{qvm} |g_{mk+q,nk}^{qv}|^2 \left(n_{qv} + \frac{1}{2} \mp \frac{1}{2} \right) \times \delta(\epsilon_{nk} - \epsilon_{mk+q} \pm \hbar\omega_{qv}) \delta(\epsilon_{nk} - E)$$

$$B(E) = \frac{1}{D(E)} \frac{2\pi}{\hbar} \sum_{\pm} \sum_{nk} \sum_{qvm} \pm \hbar\omega_{qv} |g_{mk+q,nk}^{qv}|^2 \left(n_{qv} + \frac{1}{2} \mp \frac{1}{2} \right) \times \delta(\epsilon_{nk} - \epsilon_{mk+q} \pm \hbar\omega_{qv}) \delta(\epsilon_{nk} - E)$$

$$F_{bd} = \text{Max} \left[\frac{\sqrt{3m^*}}{e} \sqrt{\frac{1}{\tau(E)} B(E)} \right], \quad E \in [CBM, CBM + E_g]$$

$$F_{bd} \approx \frac{\sqrt{3m^*}}{e} \frac{2\pi}{\hbar} g_{eff}^2 \sqrt{(2n_0 + 1) \hbar\omega_{mean} DOS_{max}}$$

$$DOS_{max} = \text{Max}[D(E)], \quad E \in [CBM, CBM + E_g]$$

- To reduce the cost of first-principles calculations, we utilized the Wannier interpolation technique.
- We developed an analytical model that shows a linear relationship between F_{bd} and DOS_{max} using appropriate approximations.

The calculated breakdown properties

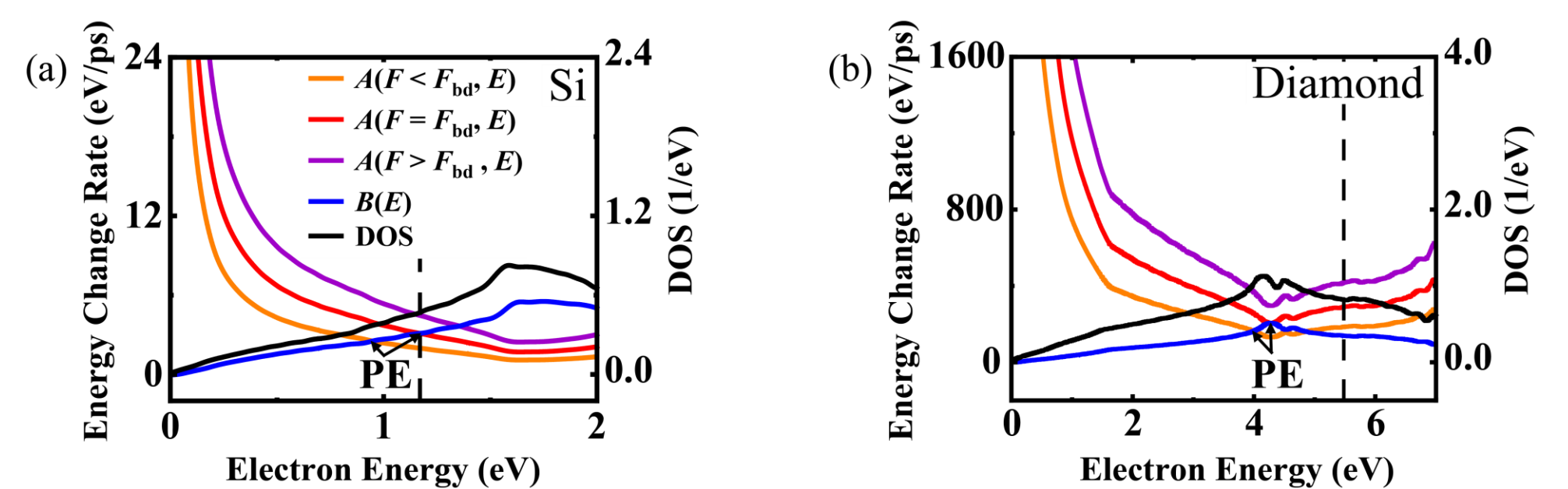


Fig. 3. The calculated energy gain rates, energy loss rates and DOS for (a) Si and (b) diamond.

- The F_{bd} is not directly related to the E_g but is determined by the PE maximum, which is governed by the DOS_{max} .

Conclusion

- We have developed an analytical model that shows a linear relationship between F_{bd} and DOS_{max} .
- By investigating the behaviors of F_{bd} under different strains in different materials, we show that the DOS_{max} is more fundamental than the band gap value in determining the F_{bd} .

References: Y. Sun, S. A. Boggs, and R. Ramprasad, Appl. Phys. Lett. **101**, 132906 (2012). Y. Sun, C. Bealing, S. Boggs, and R. Ramprasad, IEEE Electr. Insul. Mag. **29**, 8 (2013).